



eDRAM based digital computing in memory neural network accelerator with enhanced retention time

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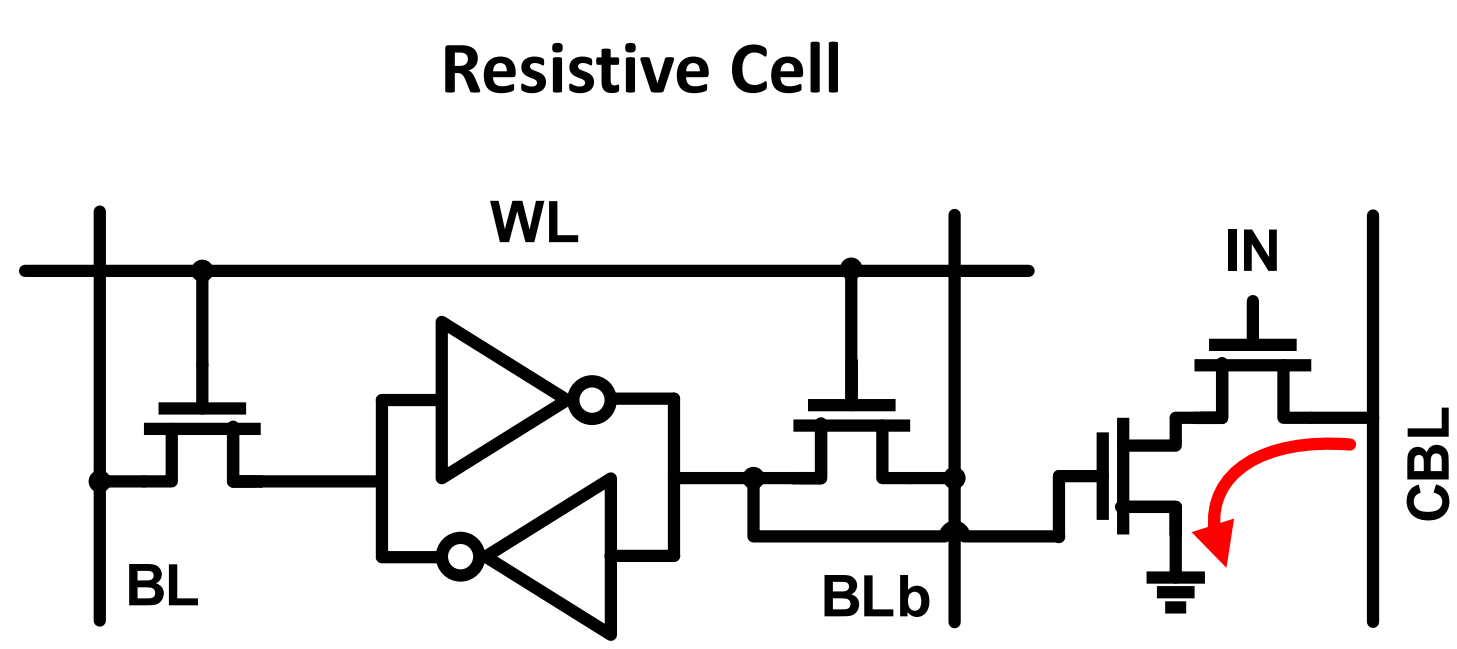
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Background

Motivations of eDRAM based NN accelerator

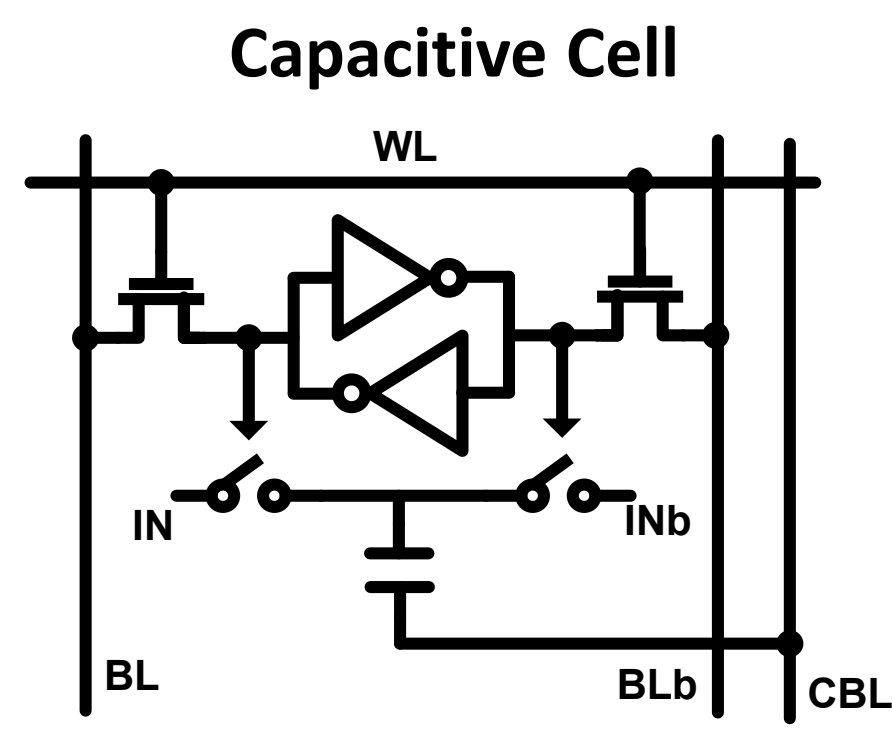
- SRAM cell based CIM design



Non-linear operation, instability due to PVT variation

SRAM cells have large cell sizes that limit their memory capacity

*CIM: Computing-in-Memory, PVT: Process, Voltage, Temperature

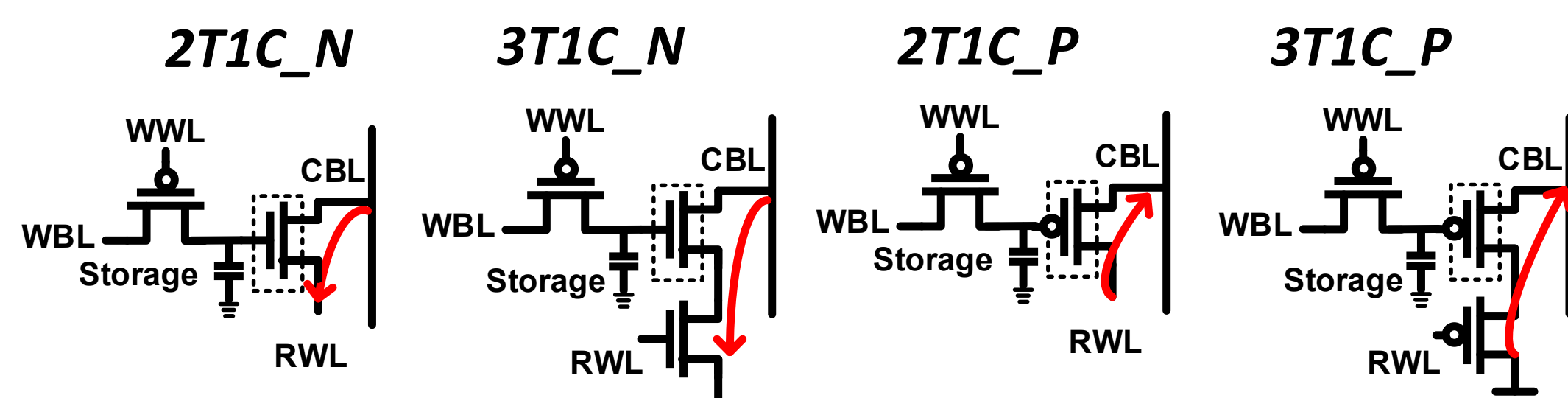


Linear operation, stability from PVT variation

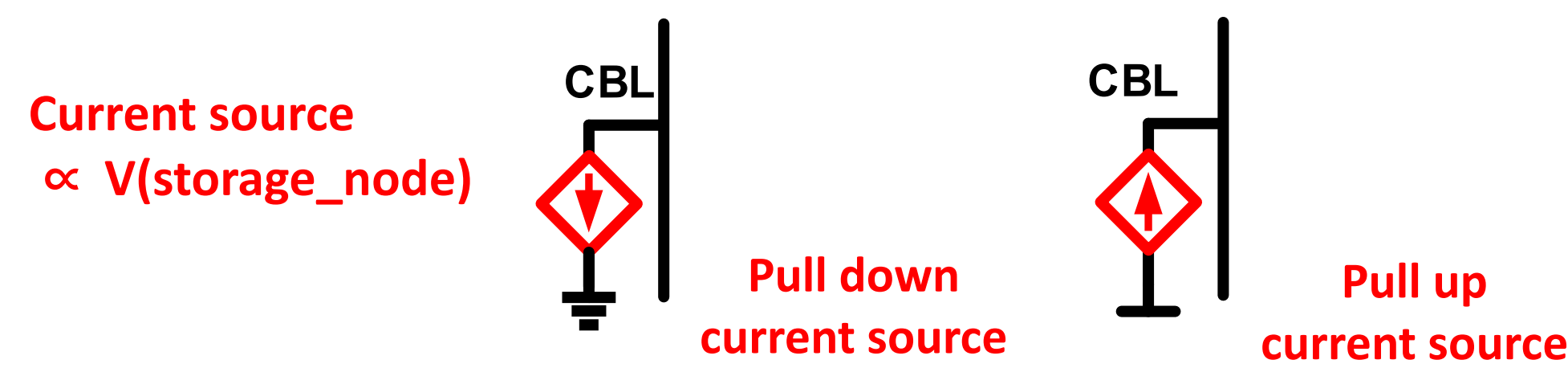
There is a need for smaller cell sizes to overcome the issue of limited memory capacity.

Previous research

- eDRAM cell based CIM design



- Modeling of eDRAM cell designs



Advantage

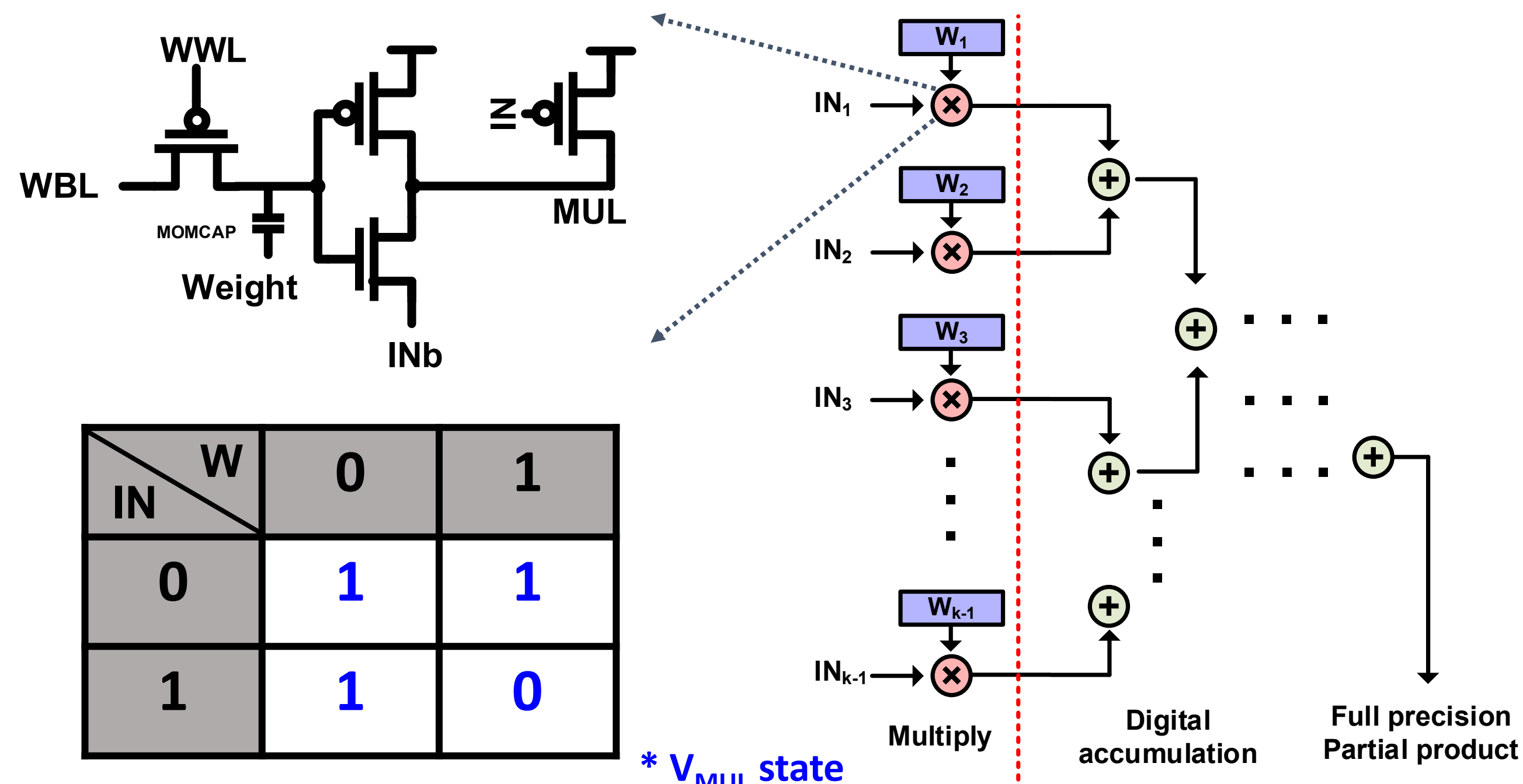
- Utilize 2 to 4 transistors to implement CIM operation with a smaller cell size.
- Logic compatible with CMOS process

Disadvantage

- Currents are vulnerable to PVT variation
- Unstable output value due to leakage current
- Short retention time

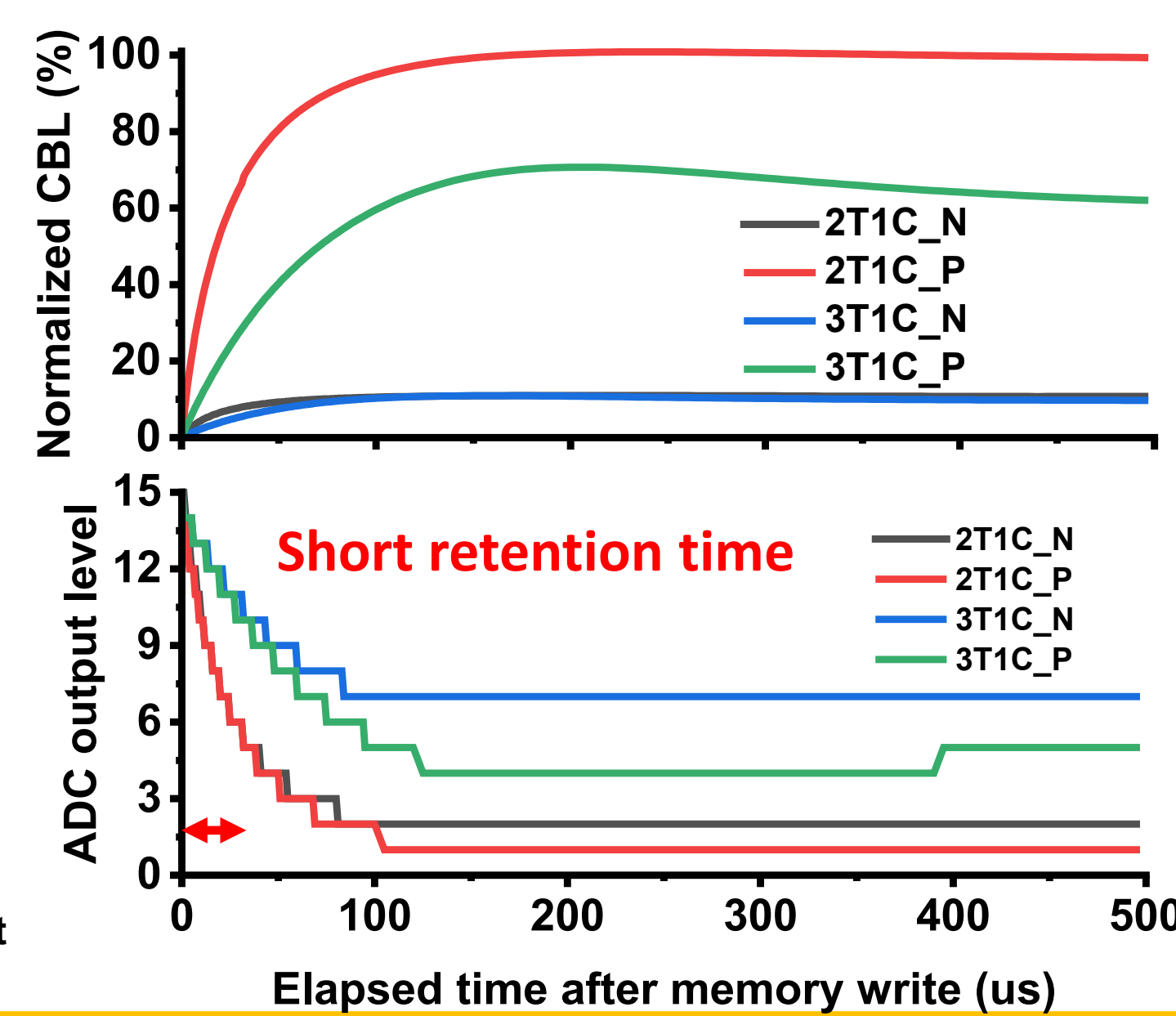
Proposed eDRAM array

Proposed cell and architecture

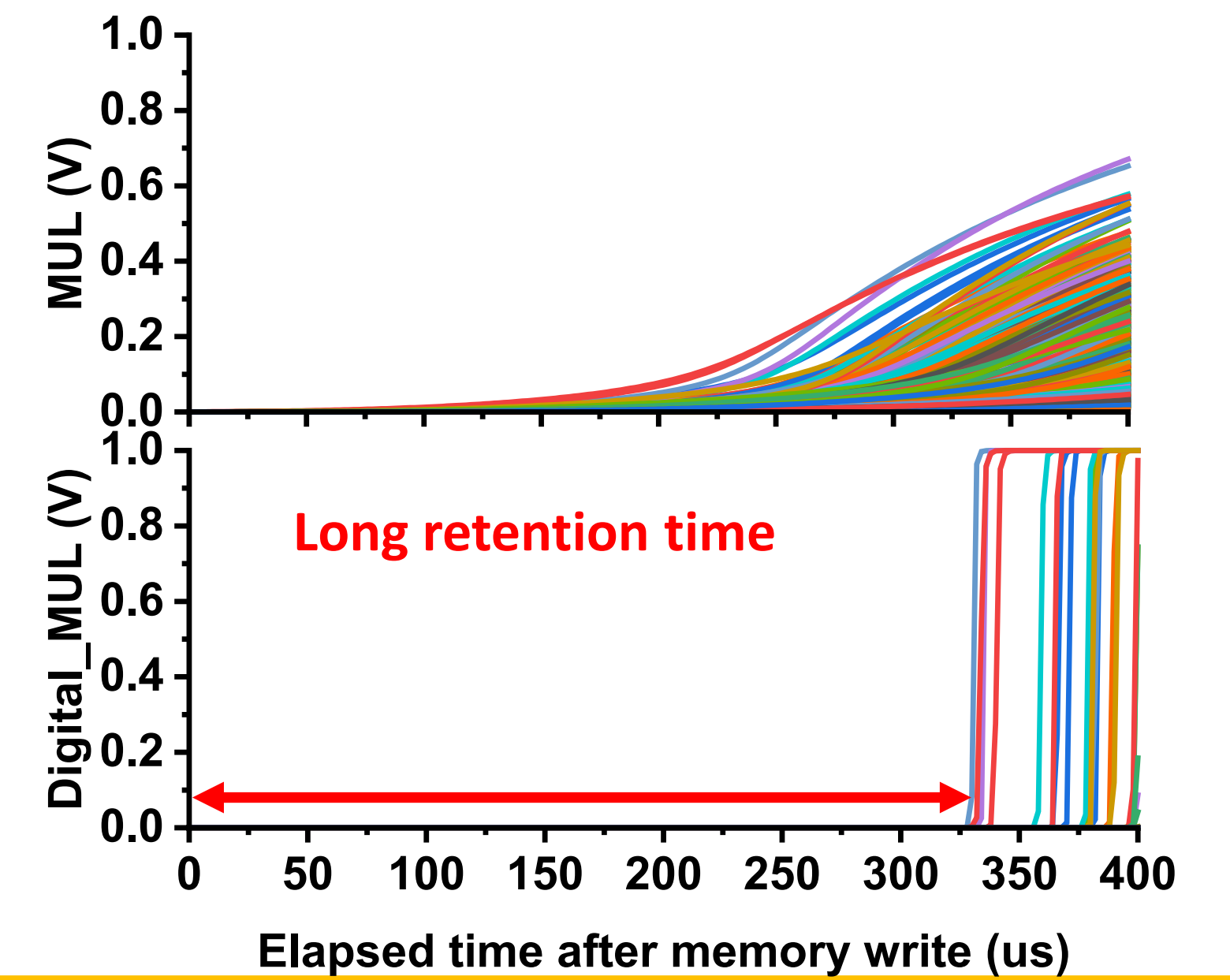


Increased retention time

- eDRAM Analog CIM

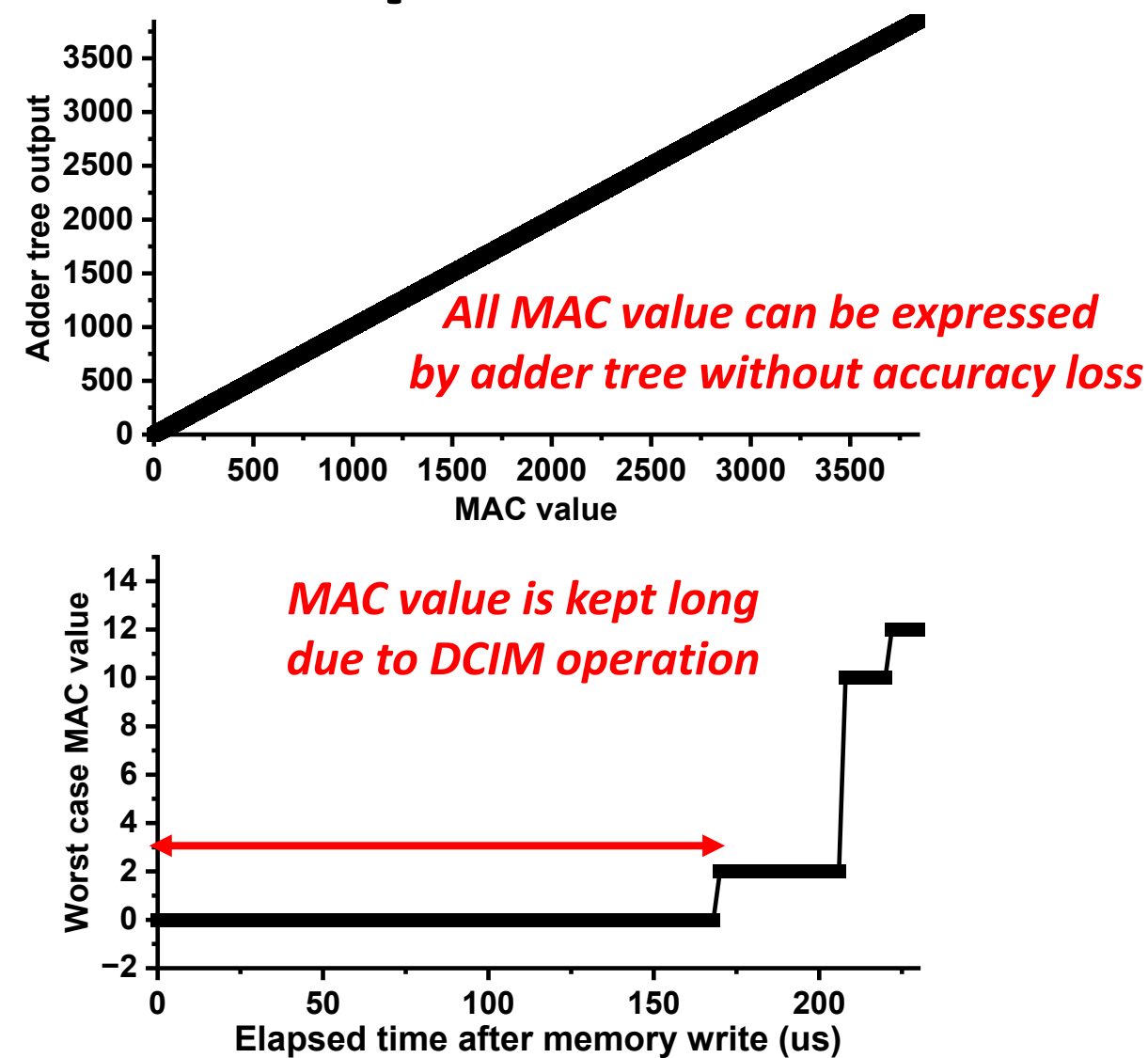


- eDRAM Digital CIM

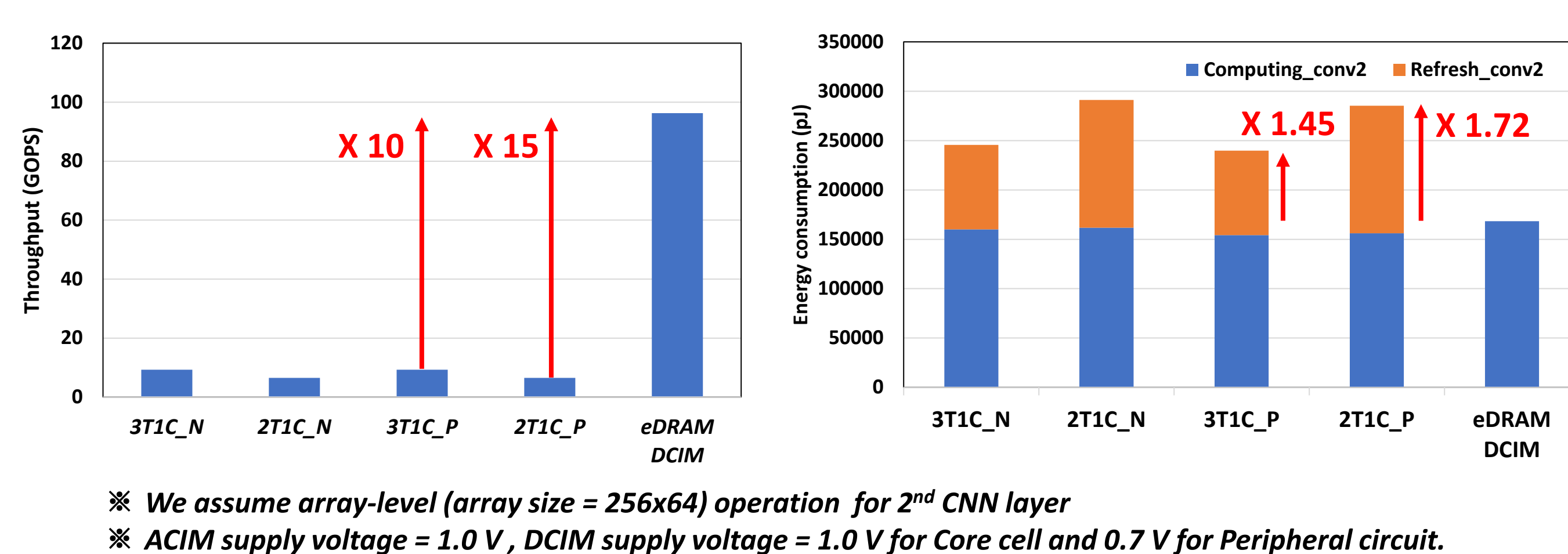


Evaluation

CIM operation

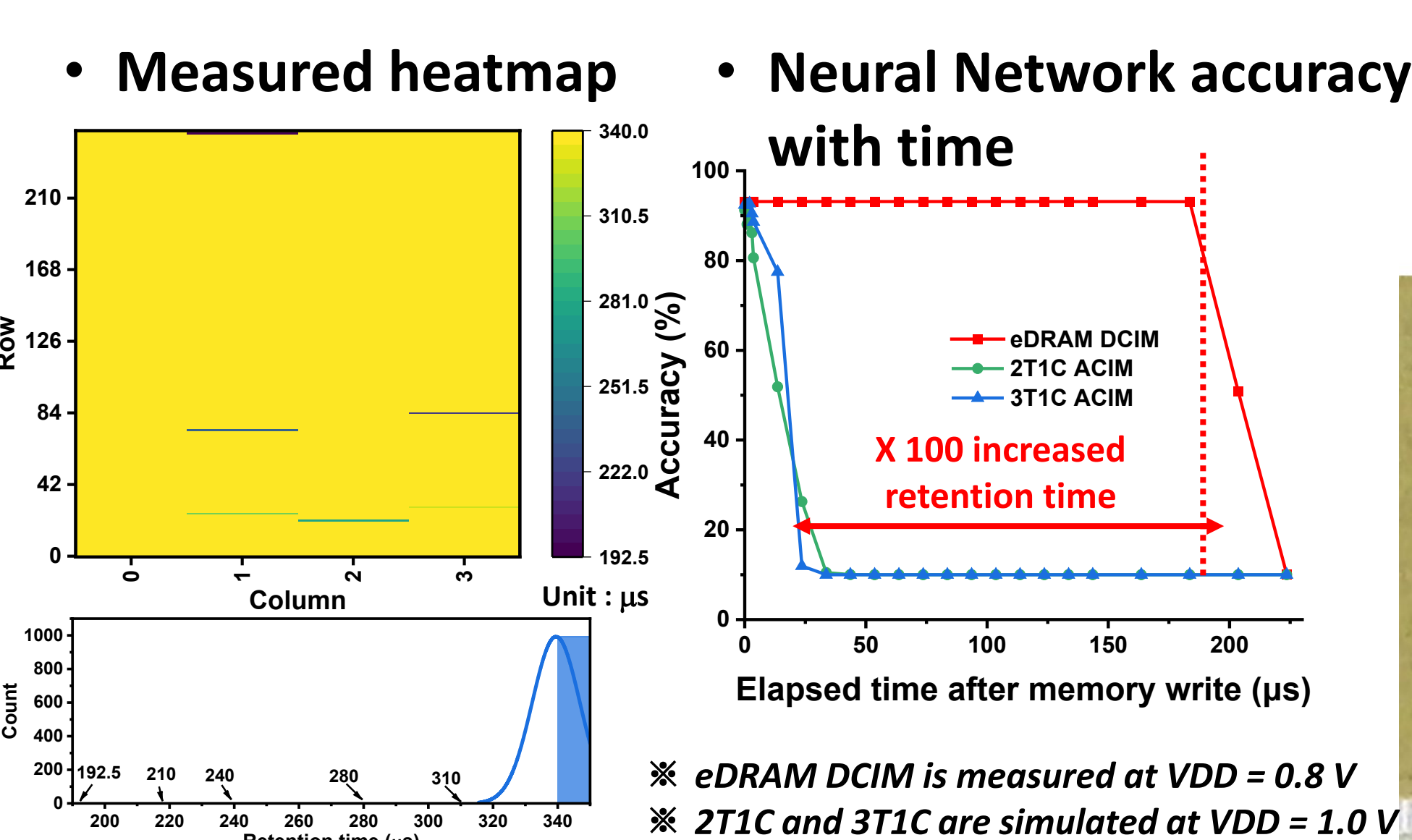


Throughput and energy consumption

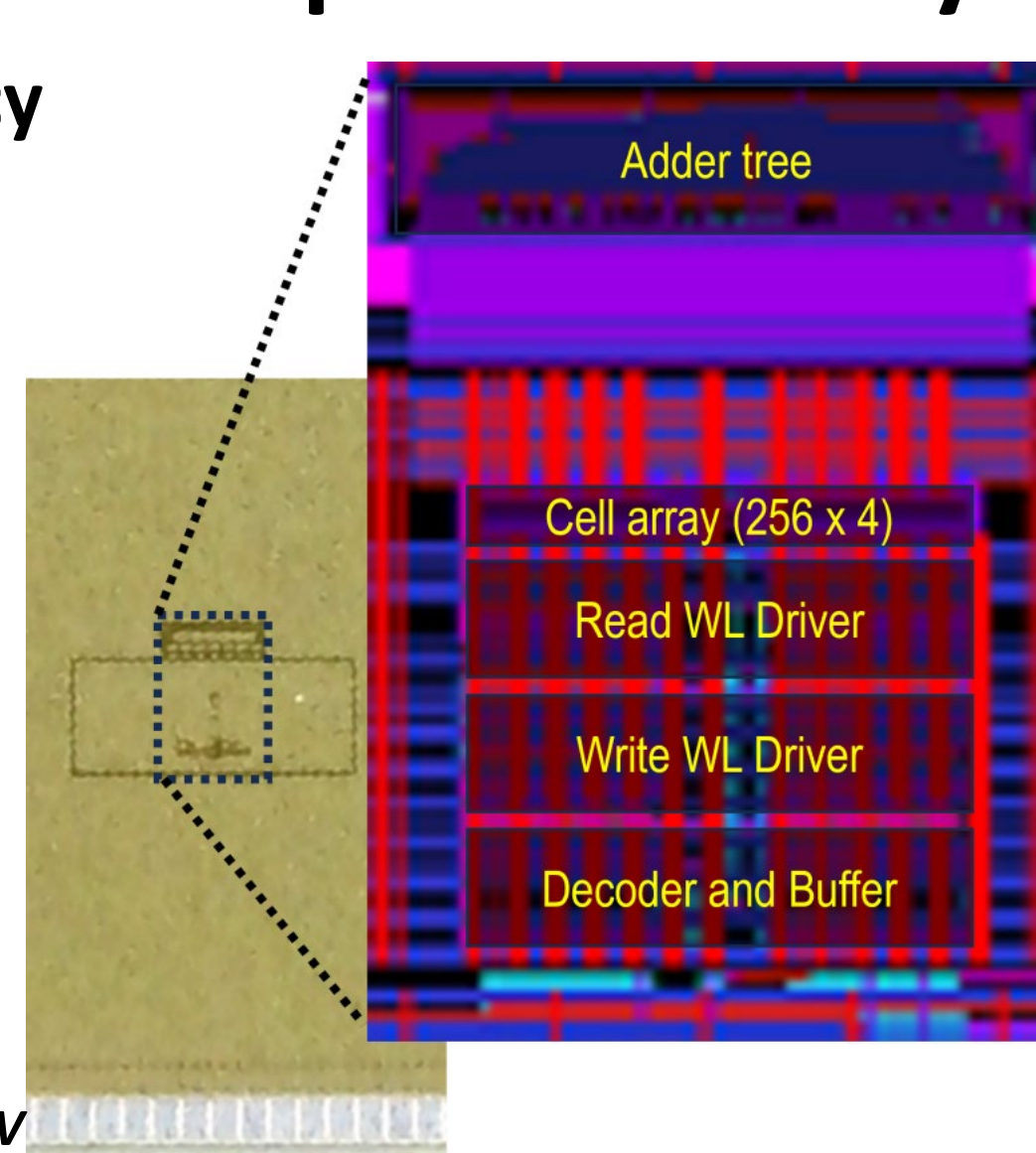


* We assume array-level (array size = 256x64) operation for 2nd CNN layer
 * ACIM supply voltage = 1.0 V, DCIM supply voltage = 1.0 V for Core cell and 0.7 V for Peripheral circuit.

Retention time



Die photo and layout of eDRAM array



Technology	28 nm CMOS
Supply voltage (V)	1.0
Frequency (MHz)	70
Input / Weight / Output	4/4/12
Array size	256x4 (1kb)
Total Area	190.7 um x 227.25 um

Conclusion

- A novel eDRAM cell mimicking a digital logic gate for digital CIM operation is proposed
- Long retention time and accurate MAC values are accomplished due to DCIM operation
- x 15 increased throughput and x 1.7 reduced energy consumption is obtained due to enhanced retention time.

Acknowledgement

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